

## REQUEST FOR ACCESS TO AN ABANDONED APPLICATION UNDER 37 CFR 1.14

Bring completed form to:  
File Information Unit  
Crystal Plaza Three, Room 1001  
2021 South Clark Place  
Arlington, VA  
Telephone: (703) 565-2733

FILED  
JUN 04 2003  
File Information Unit

In re Application of

SCHUSTER

Application Number

09/917504

Filed

7-27-01

Paper No. 8

I hereby request access under 37 CFR 1.14(e)(1)(iv) to the application file record of the above-identified ABANDONED application, which is identified in, or to which a benefit is claimed, in the following document (as shown in the attachment):

United States Patent Application Publication No. 2003/0007253, page, \_\_\_\_\_ line \_\_\_\_\_

United States Patent Number \_\_\_\_\_, column \_\_\_\_\_, line, \_\_\_\_\_ or \_\_\_\_\_

WIPO Pub. No. \_\_\_\_\_, page \_\_\_\_\_, line \_\_\_\_\_

### Related Information about Access to Pending Applications (37 CFR 1.14):

Direct access to pending applications is not available to the public but copies may be available and may be purchased from the Office of Public Records upon payment of the appropriate fee (37 CFR 1.19(b)), as follows:  
For published applications that are still pending, a member of the public may obtain a copy of:

- the file contents;
- the pending application as originally filed; or
- any document in the file of the pending application.

For unpublished applications that are still pending:

- (1) If the benefit of the pending application is claimed under 35 U.S.C. 119(e), 120, 121, or 365 in another application that has: (a) issued as a U.S. patent, or (b) published as a statutory invention registration, a U.S. patent application publication, or an international patent application publication in accordance with PCT Article 21(2), a member of the public may obtain a copy of:

- the file contents;
- the pending application as originally filed; or
- any document in the file of the pending application.

- (2) If the application is incorporated by reference or otherwise identified in a U.S. patent, a statutory invention registration, a U.S. patent application publication, or an international patent application publication in accordance with PCT Article 21(2), a member of the public may obtain a copy of:

- the pending application as originally filed.

Hendrick

Signature

HENDRICK TRAN

Typed or printed name

Registration Number, if applicable

703-629-7617

Telephone Number

Date

1-4-05

FOR PTO USE ONLY

Approved by:

(Initials)

JUN 04 2003

Unit:

File Information Unit

This collection of information is required by 37 CFR 1.14. The information is required to obtain or retain a benefit by the publication to the USPTO (in process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 12 minutes to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS OFFICE. Send only TO: File Information Unit, Crystal Plaza Three, Room 1001, 2021 South Clark Place, Arlington, VA.



US 20030007253A1

8

(19) **United States**(12) **Patent Application Publication** (10) Pub. No.: **US 2003/0007253 A1**  
Schuster et al. (43) Pub. Date: **Jan. 9, 2003**(54) **LARGE-APERTURED PROJECTION LENS  
WITH MINIMAL DIAPHRAGM ERROR**Nov. 30, 1998 (DE)..... 198 55 157.6  
May 14, 1999 (DE)..... 199 22 209.6  
Apr. 9, 1999 (DE)..... 199 42 281.8(76) Inventors: **Karl-Heinz Schuster, Königsbrunn  
(DE); Wilhelm Ulrich, Aalen (DE)**Correspondence Address:  
**M. Robert Kestenbaum**  
11011 Bermuda Dunes NE  
Albuquerque, NM 87111 (US)**Publication Classification**(51) Int. Cl.<sup>7</sup> ..... **G03B 27/42; G02B 3/00;  
G02B 7/00; G02B 13/00;  
G02B 13/04**  
(52) U.S. Cl. .... **359/642; 359/749**(21) Appl. No.: **09/917,504**(22) Filed: **Jul. 27, 2001****Related U.S. Application Data**(63) Continuation-in-part of application No. PCT/EP99/  
09235, filed on Nov. 27, 1999.(30) **Foreign Application Priority Data**

Nov. 30, 1998 (DE)..... 198 55 108.8

(57) **ABSTRACT**

The invention relates to a large-apertured microlithography projection lens. The diaphragm error is also systematically corrected, so that the pupil plane is slightly curved and the lens can be stopped down without comprising quality. The system diaphragm of the projection lens is located in the area of the last lens cluster of positive refractive power on the image side. The telecentrics of the projection lens remain stable on the image side during stopping down.

